

FORMING STEP OF SILICON NITRIDE OXIDE FILM
(Si Nx By Oz) 103a BY SPUTTERING

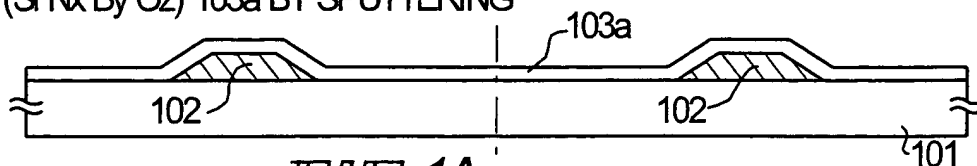


FIG. 1A

FORMING STEP OF INSULATING FILM
103b AND SEMICONDUCTOR FILM



FIG. 1B

LASER CRYSTALLIZATION STEP

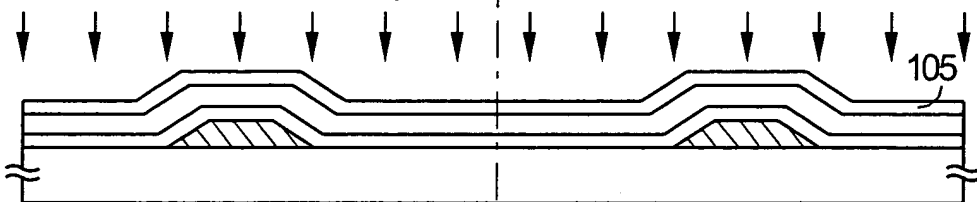


FIG. 1C

BACK EXPOSURE STEP

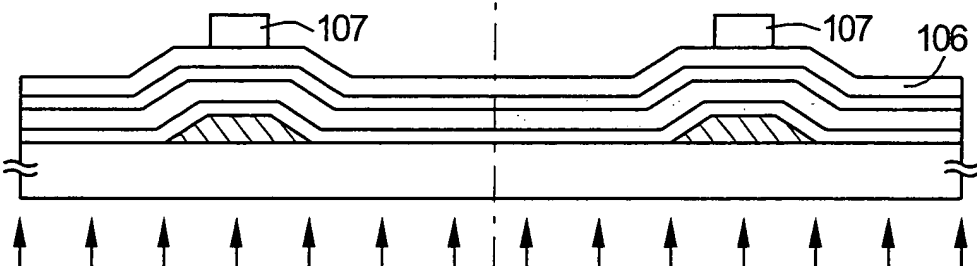


FIG. 1D

ETCHING STEP

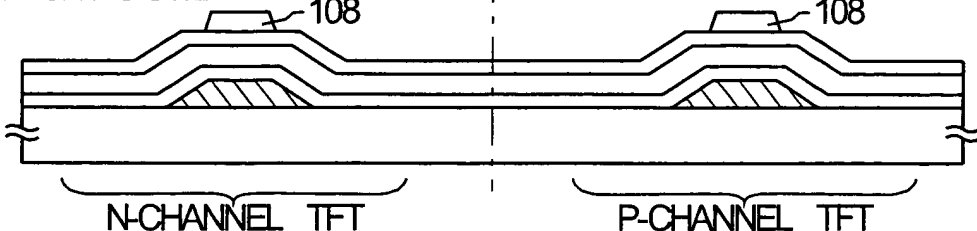


FIG. 1E

DOPING STEP (FORMING STEP OF N^+ REGION)

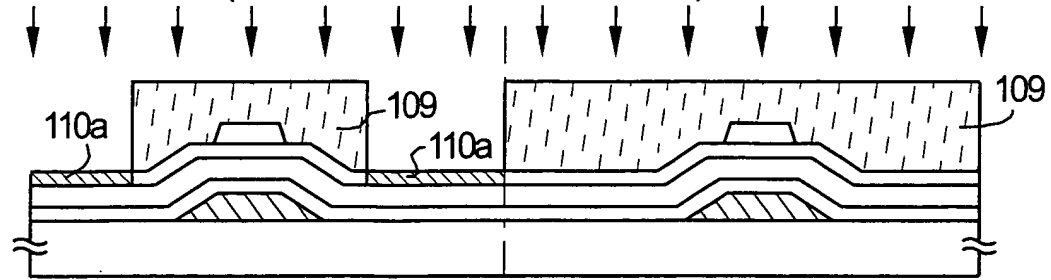


FIG. 2A

FORMING STEP OF INSULATING FILM 111

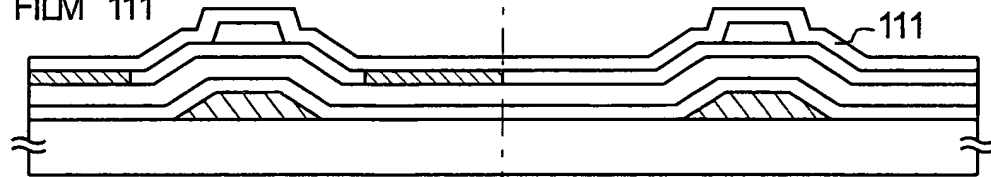


FIG. 2B

DOPING STEP (FORMING STEP OF n^- REGION)

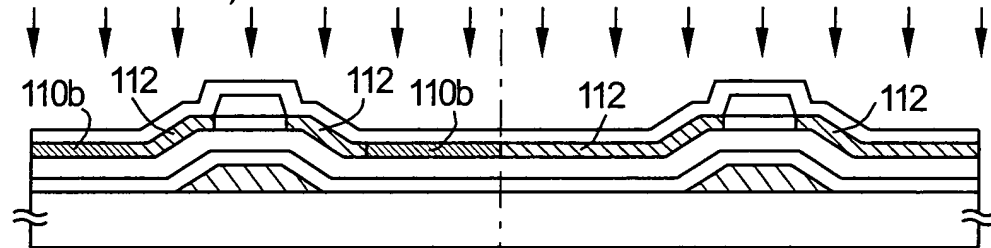
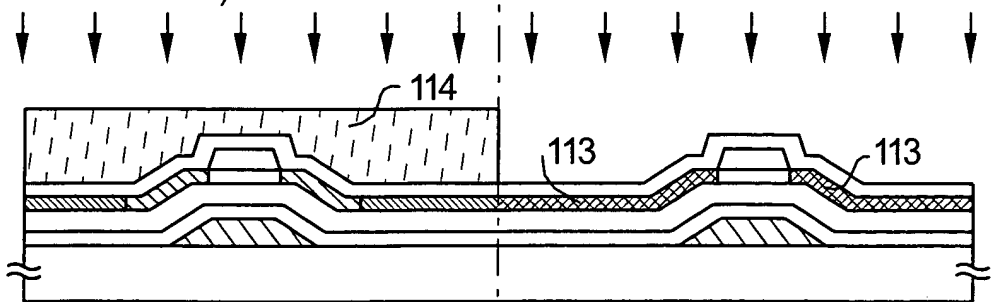


FIG. 2C

DOPING STEP (FORMING STEP OF P^+ REGION)



N-CHANNEL TYPE TFT

P-CHANNEL TYPE TFT

FIG. 2D

ACTIVATION STEP

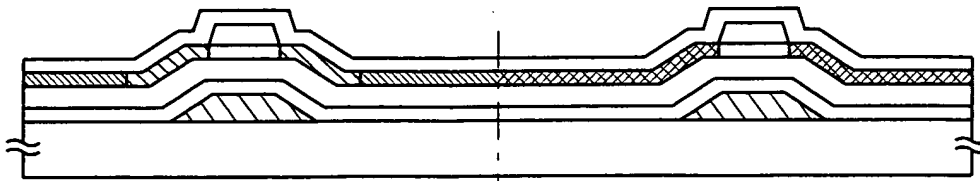


FIG. 3A

PATTERNING STEP

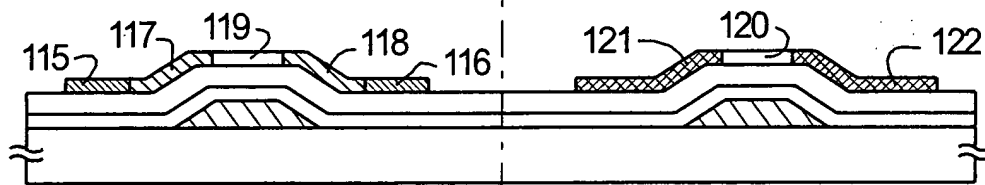


FIG. 3B

FORMING STEP OF INTERLAYER
INSULATING FILM

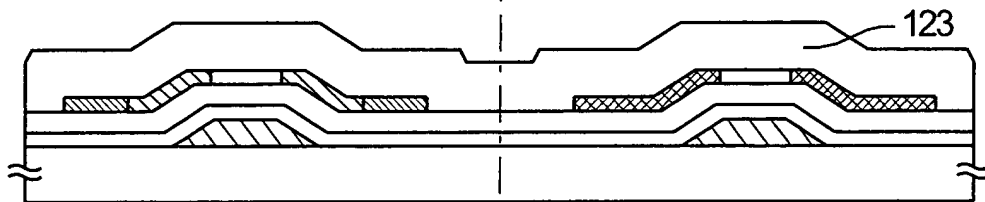
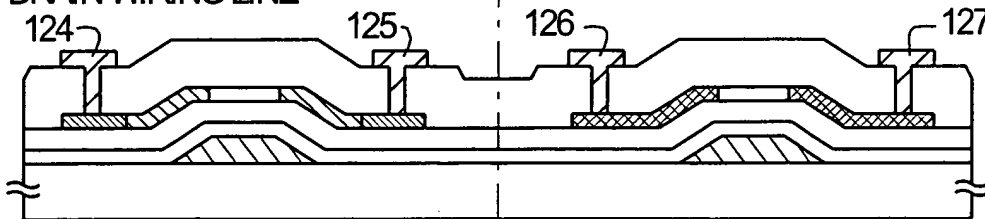


FIG. 3C

FORMING STEP OF SOURCE
WIRING LINE AND
DRAIN WIRING LINE



N-CHANNEL TYPE TFT

P-CHANNEL TYPE TFT

FIG. 3D

FIG. 4A

FORMING STEP OF SILICON NITRIDE OXIDE FILM
($\text{Si}_x\text{N}_y\text{O}_z$) 103a BY SPUTTERING

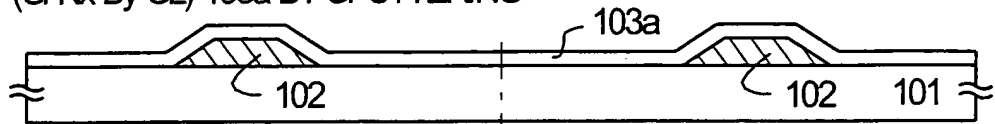


FIG. 4B

FORMING STEP OF INSULATING FILM
103b AND SEMICONDUCTOR FILM

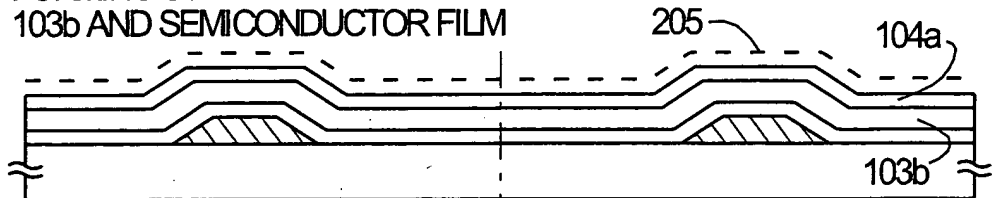


FIG. 4C

CRYSTALLIZATION STEP BY
HEAT TREATMENT

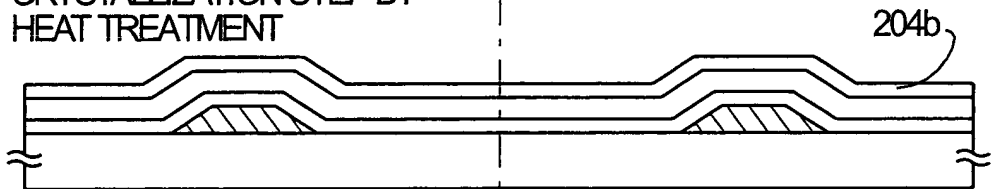


FIG. 4D

LASER IRRADIATION STEP

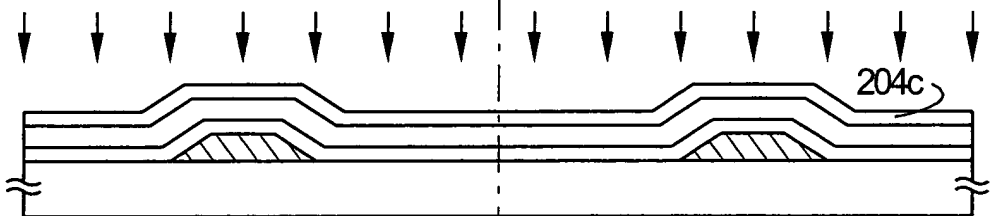


FIG. 4E

BACK EXPOSURE STEP

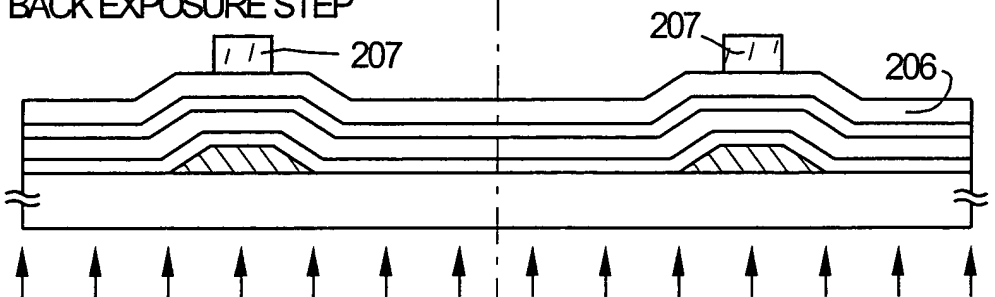
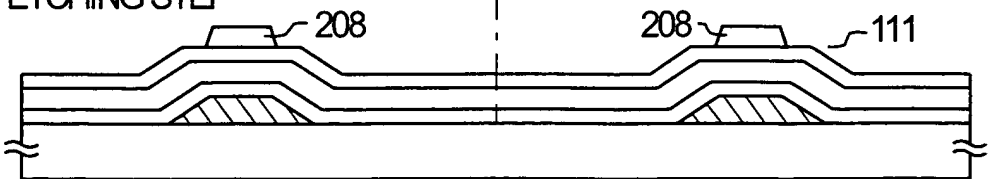


FIG. 4F

ETCHING STEP



N-CHANNEL TYPE TFT

P-CHANNEL TYPE TFT

DOPING STEP (FORMING STEP OF n^+ REGION)

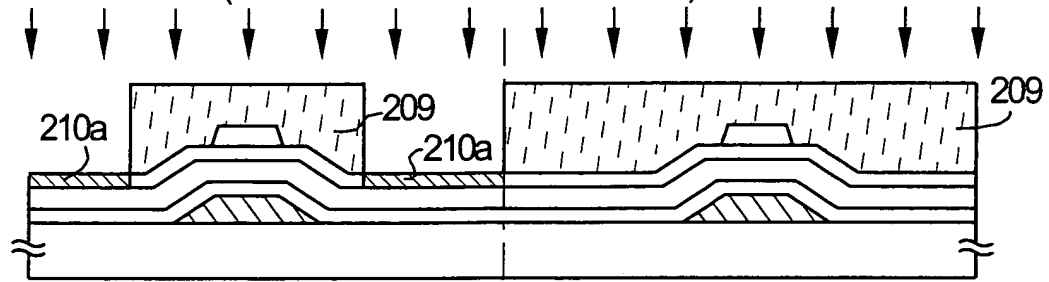


FIG. 5A

FORMING STEP OF INSULATING FILM 211

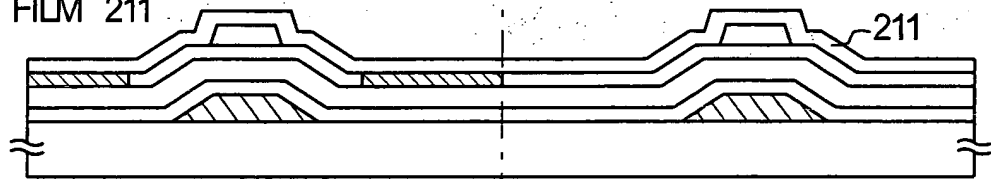


FIG. 5B

DOPING STEP (FORMING STEP OF n^- REGION)

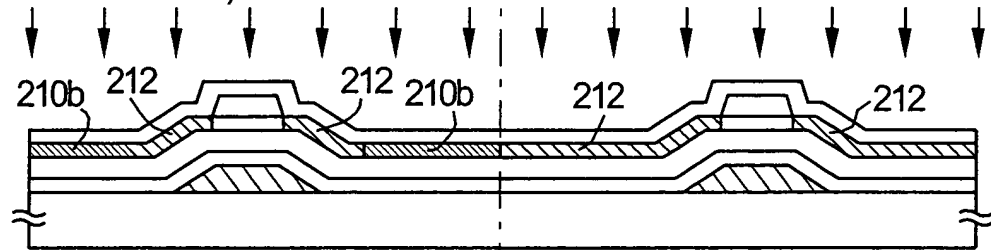
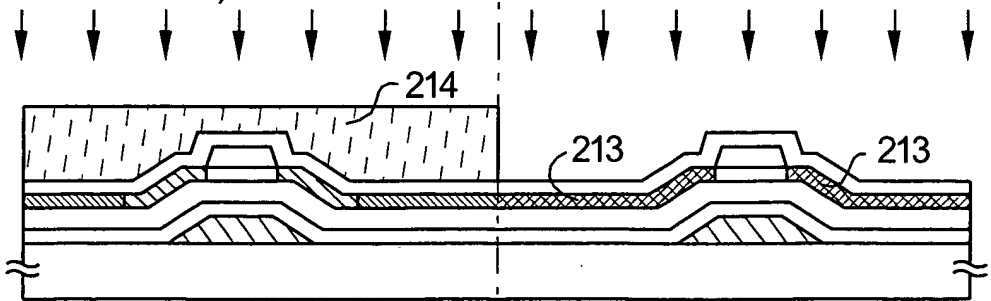


FIG. 5C

DOPING STEP (FORMING STEP OF p^+ REGION)



N-CHANNEL TYPE TFT

P-CHANNEL TYPE TFT

FIG. 5D

ACTIVATION AND GETTERING STEP

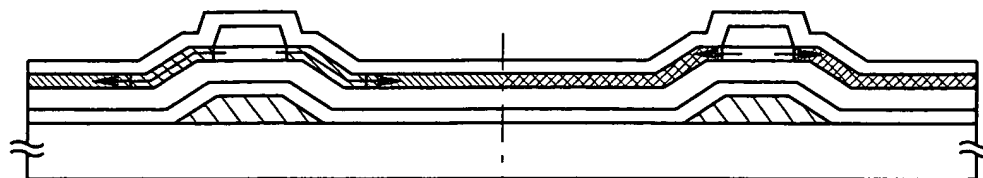


FIG. 6A

PATTERNING STEP

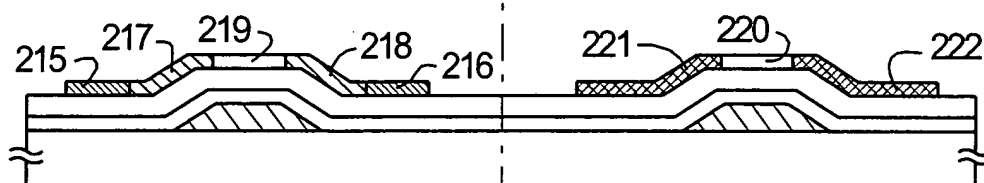


FIG. 6B

FORMING STEP OF INTERLAYER INSULATING FILM

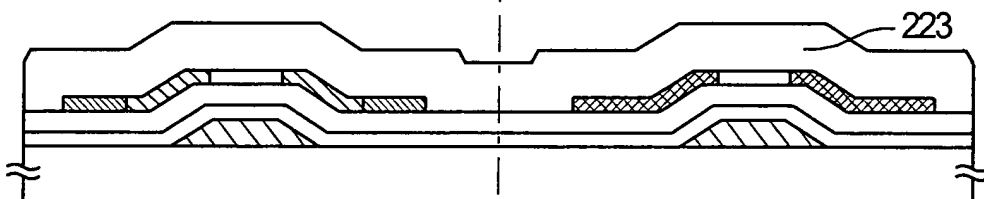
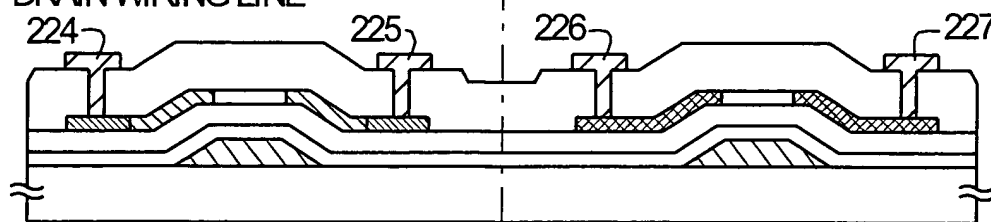


FIG. 6C

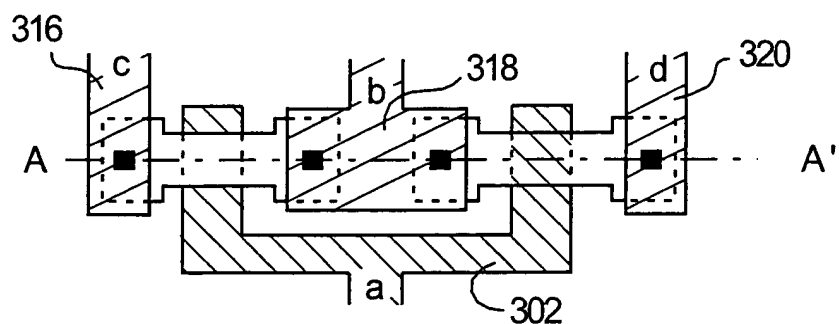
FORMING STEP OF SOURCE WIRING LINE AND DRAIN WIRING LINE



N-CHANNEL TYPE TFT

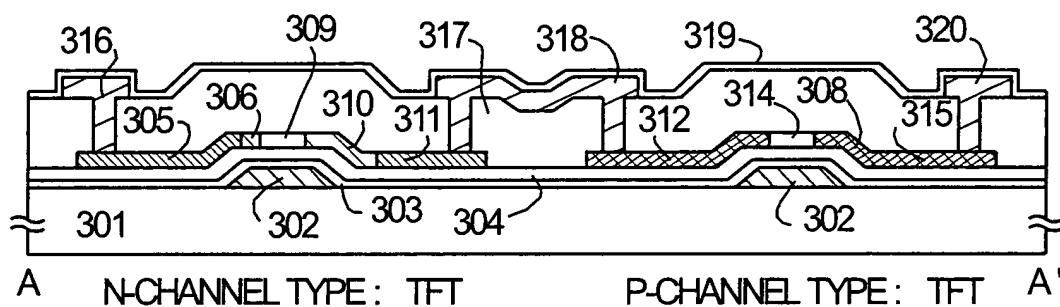
P-CHANNEL TYPE TFT

FIG. 6D



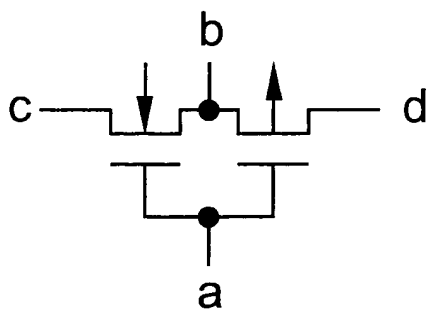
TOP VIEW OF CMOS CIRCUIT

FIG. 7A



SECTIONAL STRUCTURE VIEW ALONG A-A'

FIG. 7B



CIRCUIT DIAGRAM OF CMOS

FIG. 7C

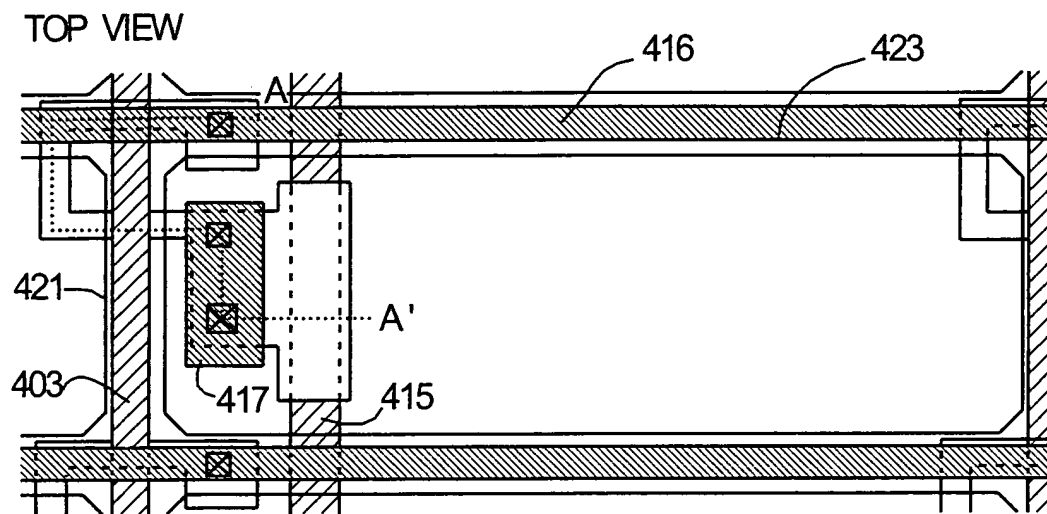


FIG. 8A

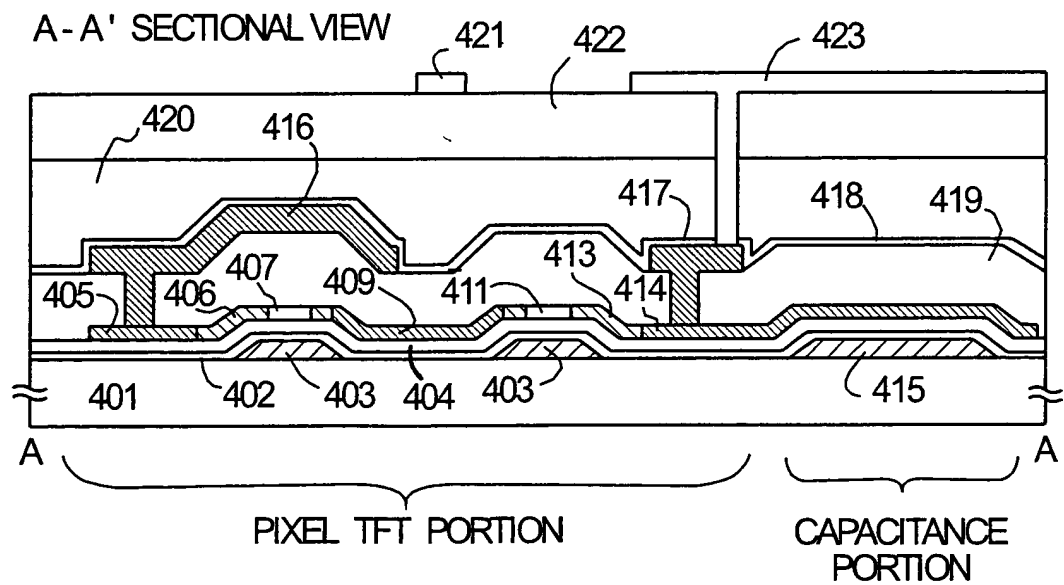


FIG. 8B



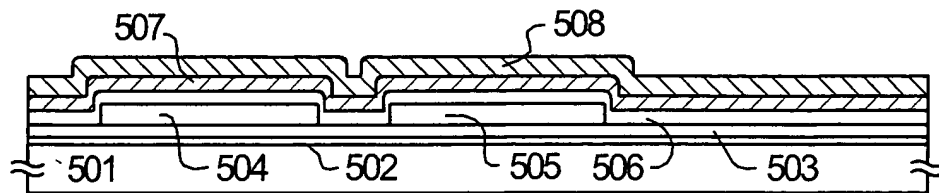


FIG. 9A

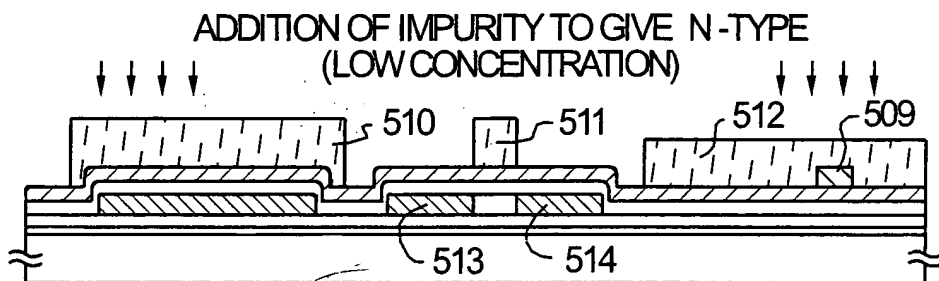


FIG. 9B

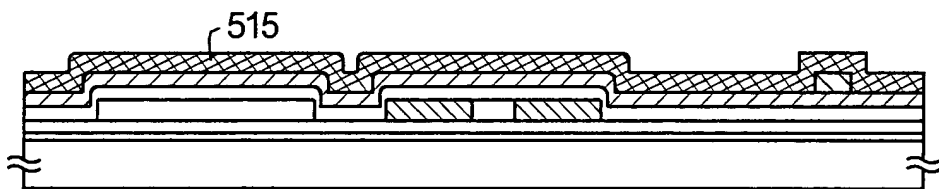


FIG. 9C

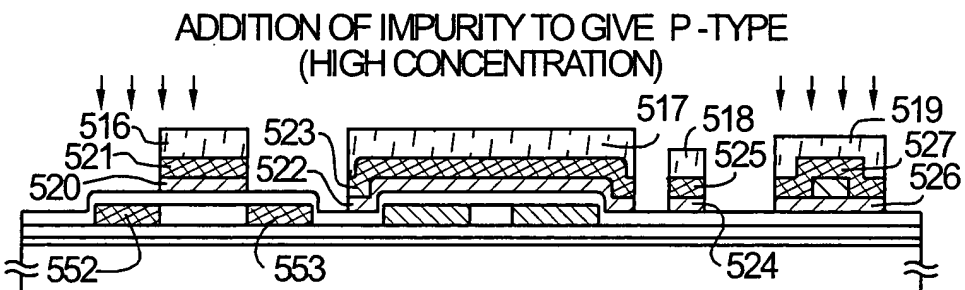


FIG. 9D

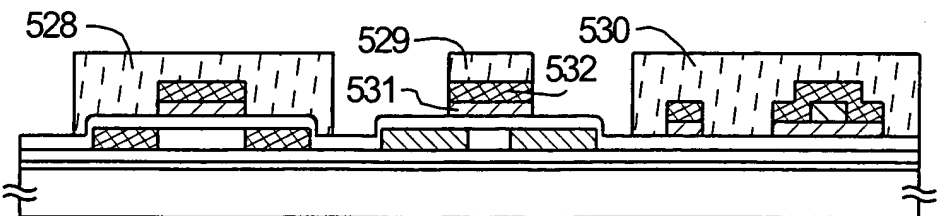


FIG. 9E

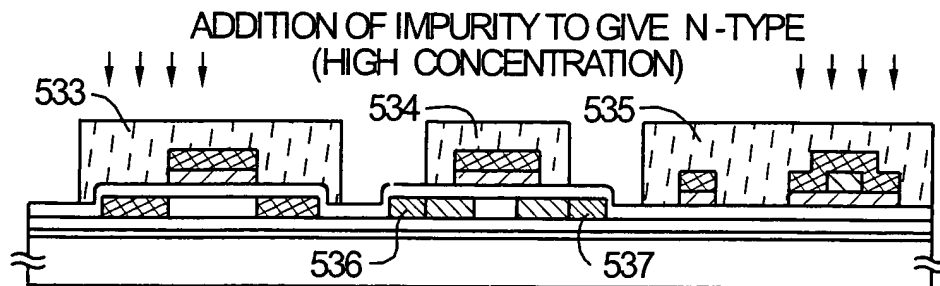


FIG. 10A

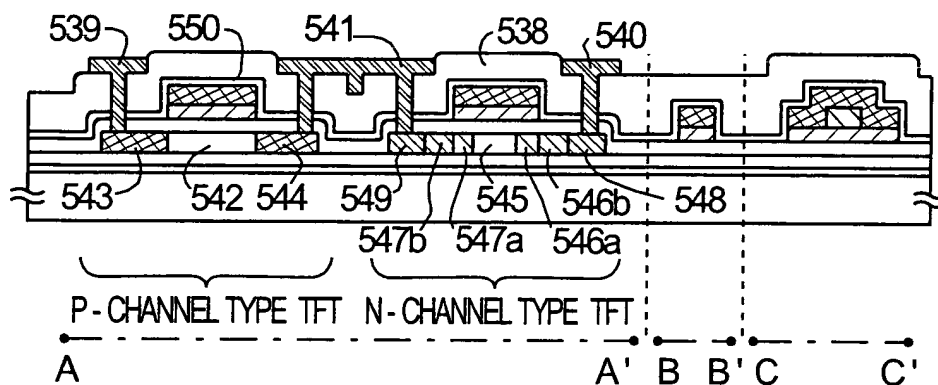
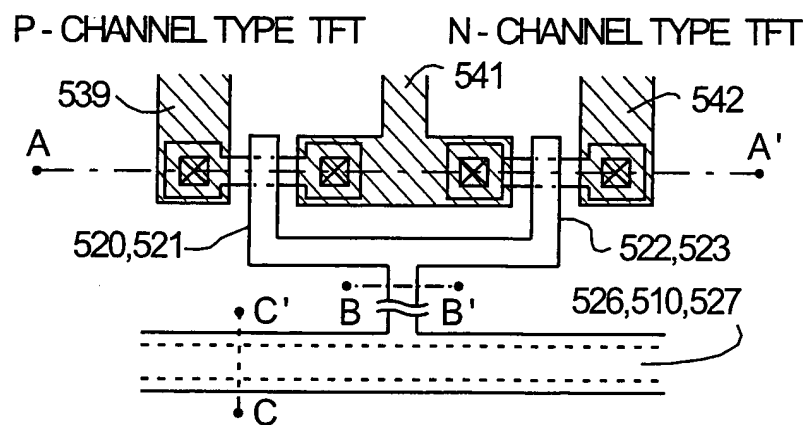


FIG. 10B



TOP VIEW OF CMOS CIRCUIT

FIG. 10C

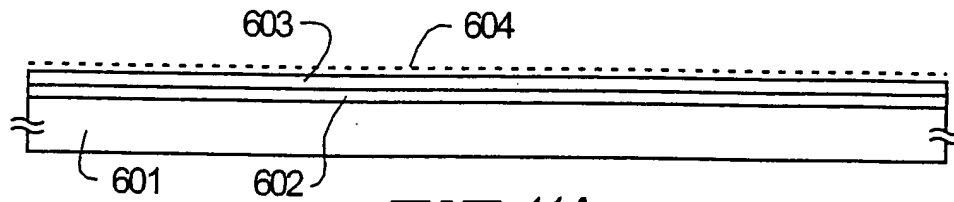


FIG. 11A

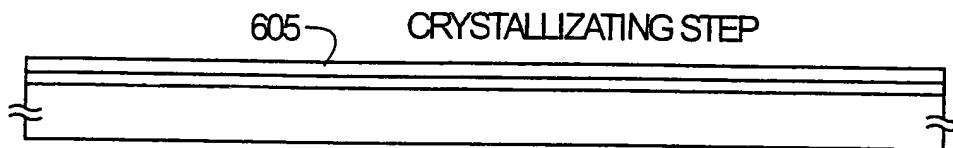


FIG. 11B

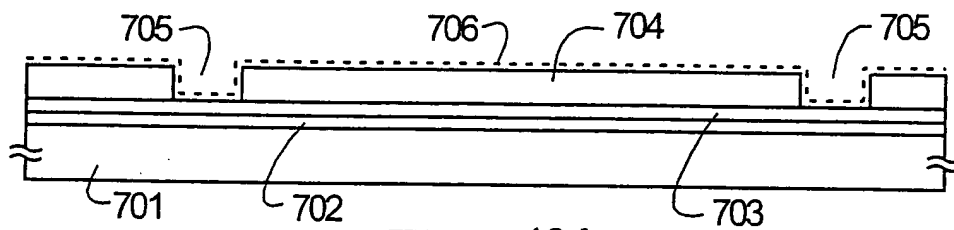


FIG. 12A

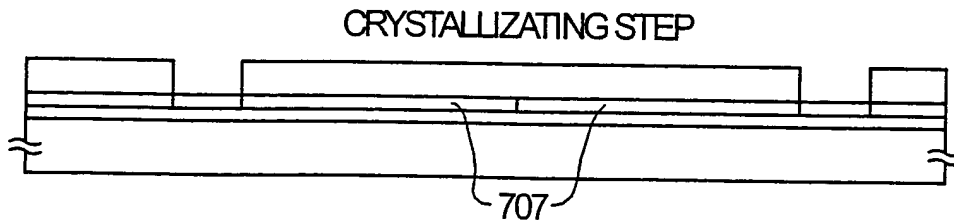
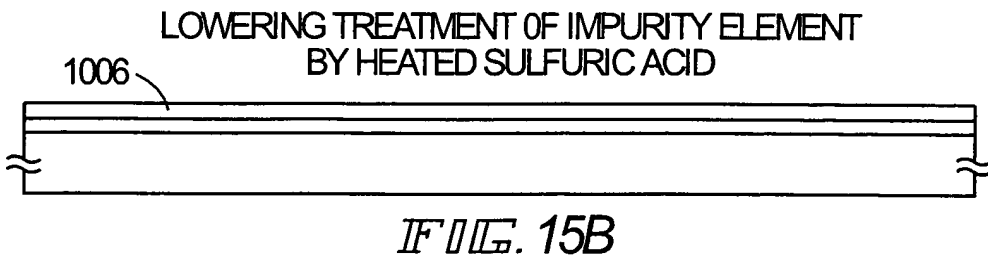
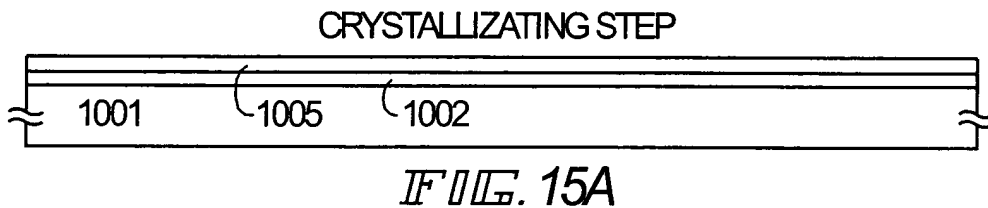
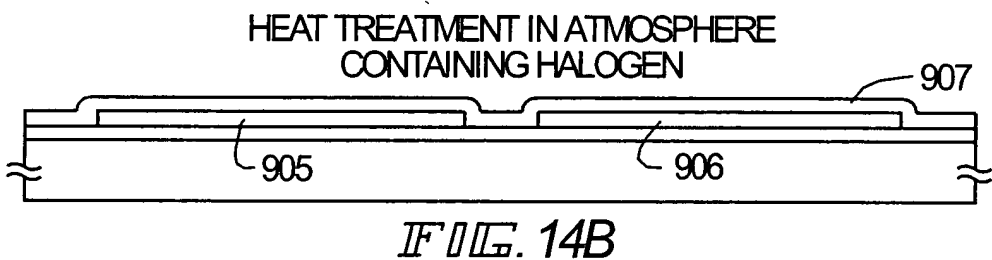
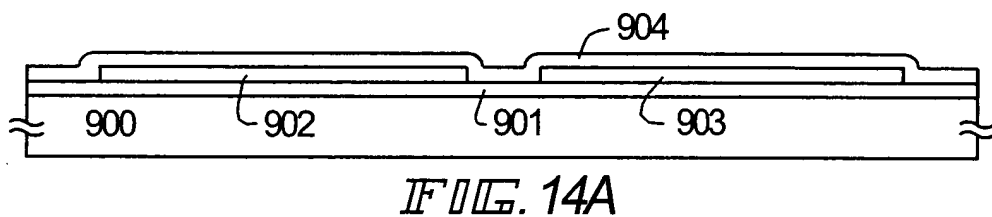
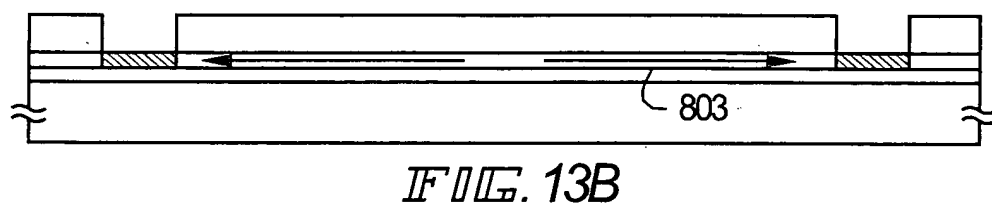
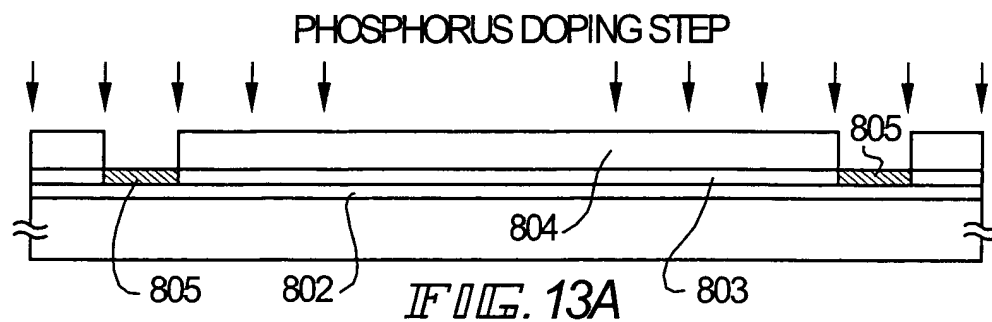


FIG. 12B



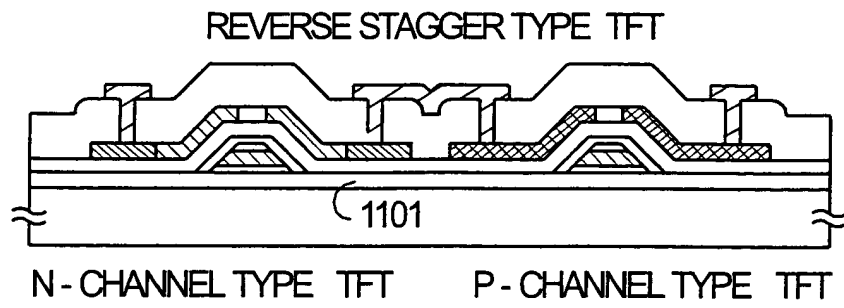


FIG. 16A

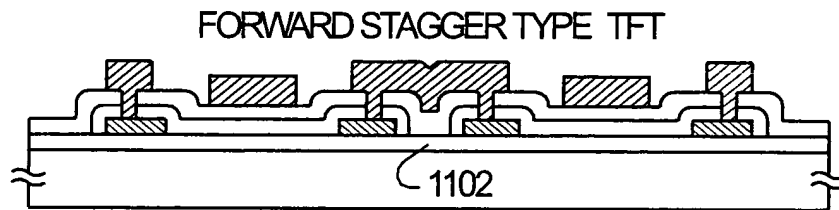


FIG. 16B

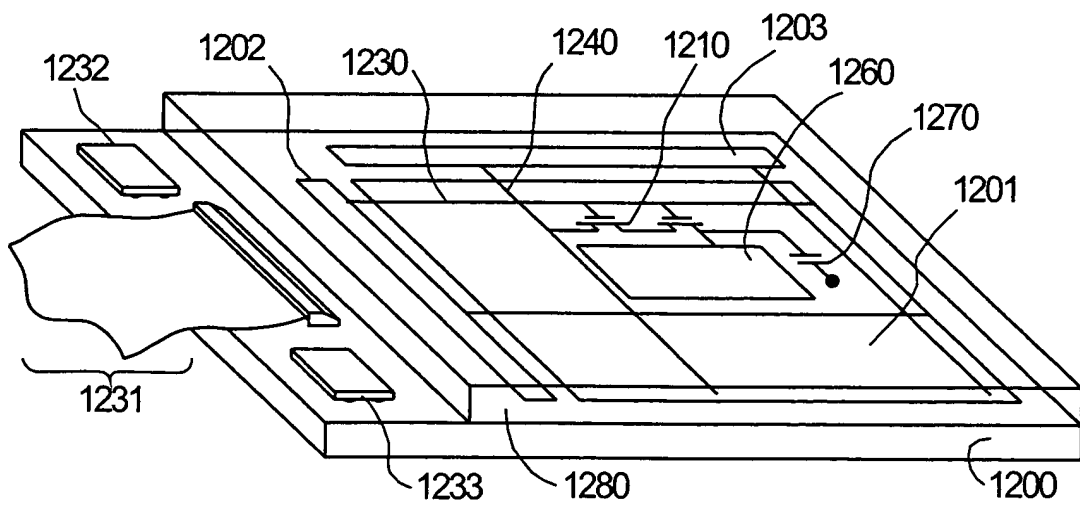


FIG. 17



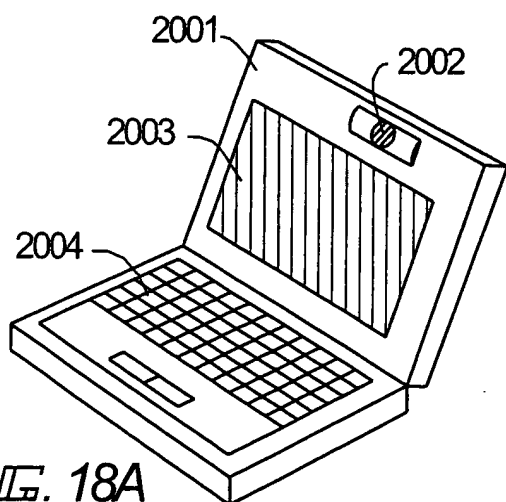


FIG. 18A

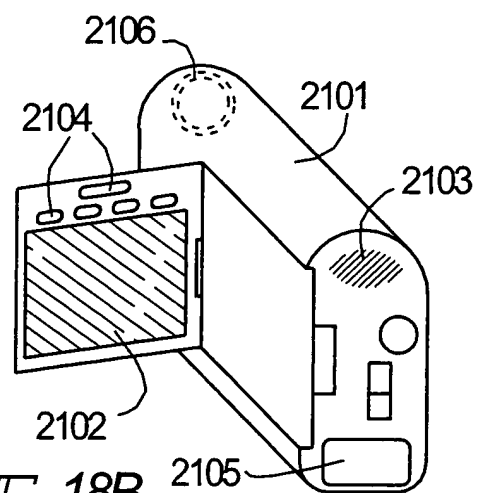


FIG. 18B

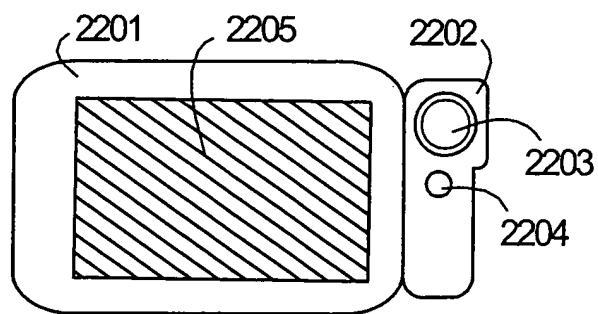


FIG. 18C

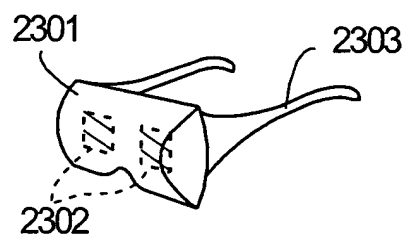


FIG. 18D

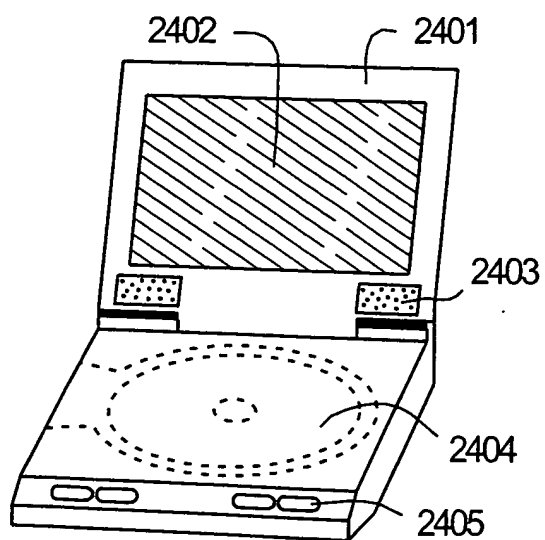


FIG. 18E

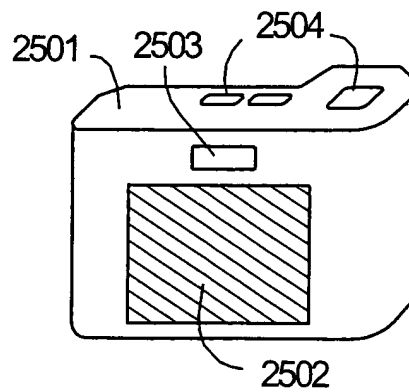


FIG. 18F



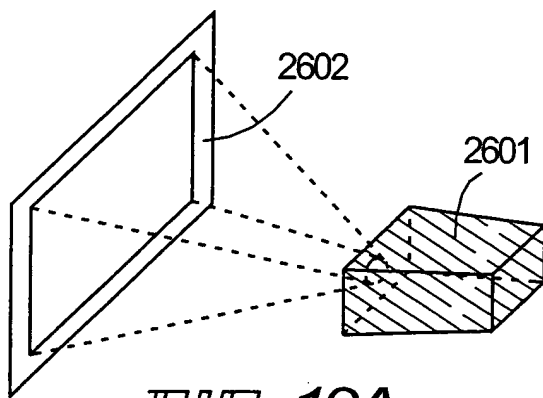


FIG. 19A

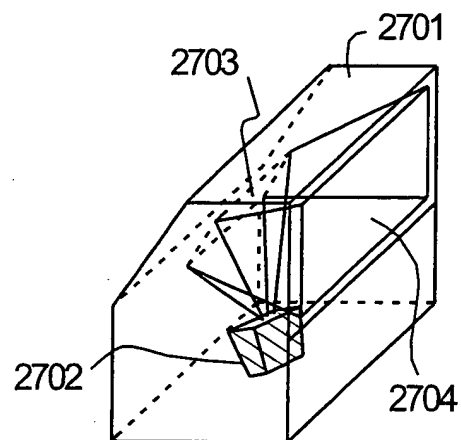
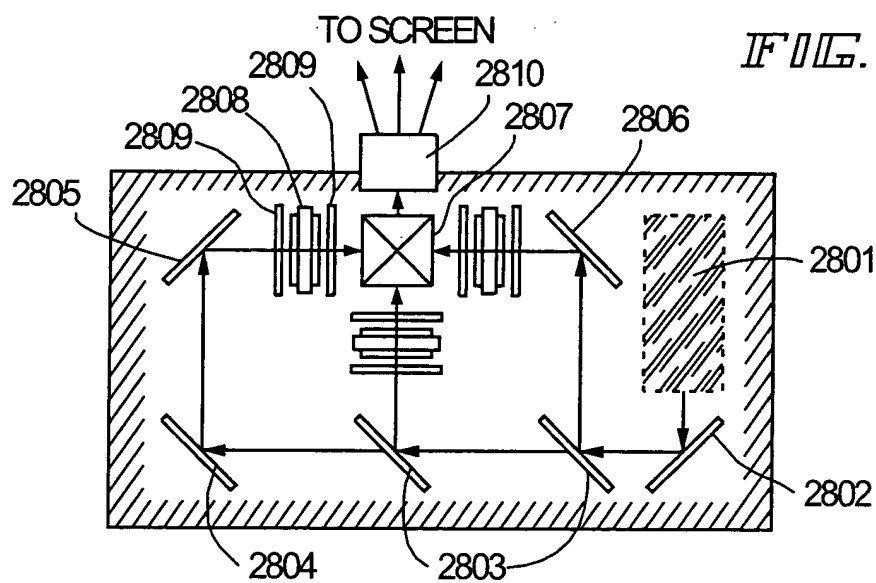
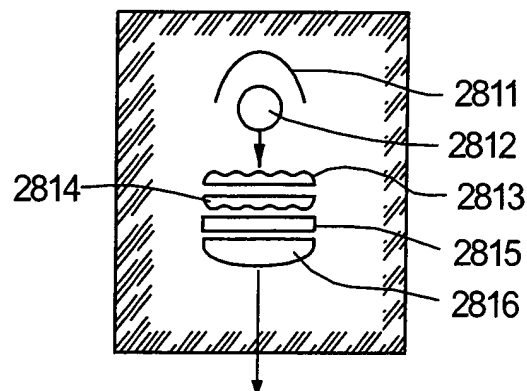


FIG. 19B



PROJECTION DEVICE (THREE PLATE TYPE)

FIG. 19C



LIGHT SOURCE OPTICAL SYSTEM

FIG. 19D

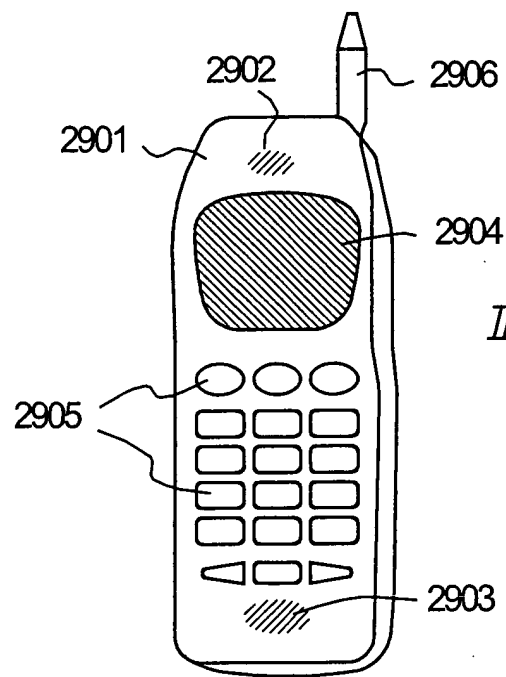


FIG. 20A

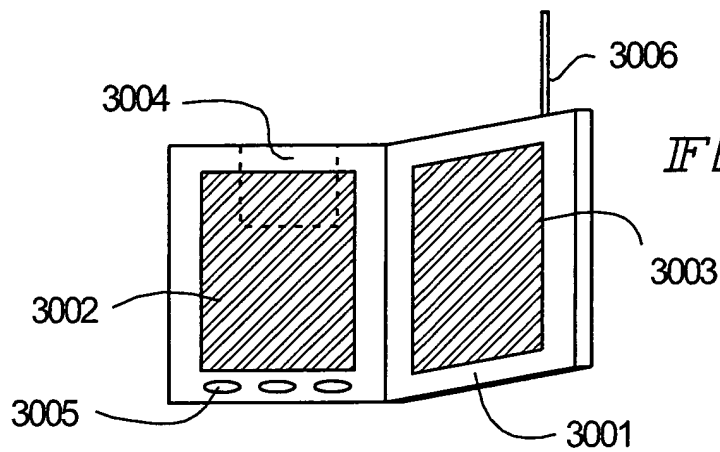


FIG. 20B

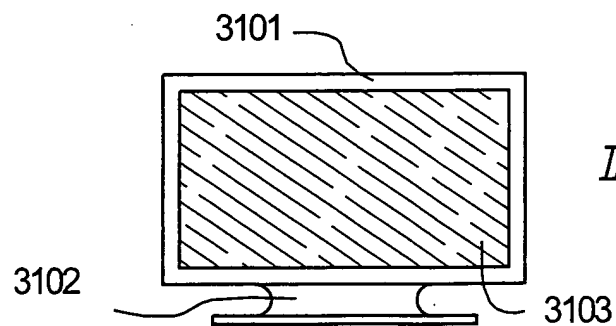


FIG. 20C

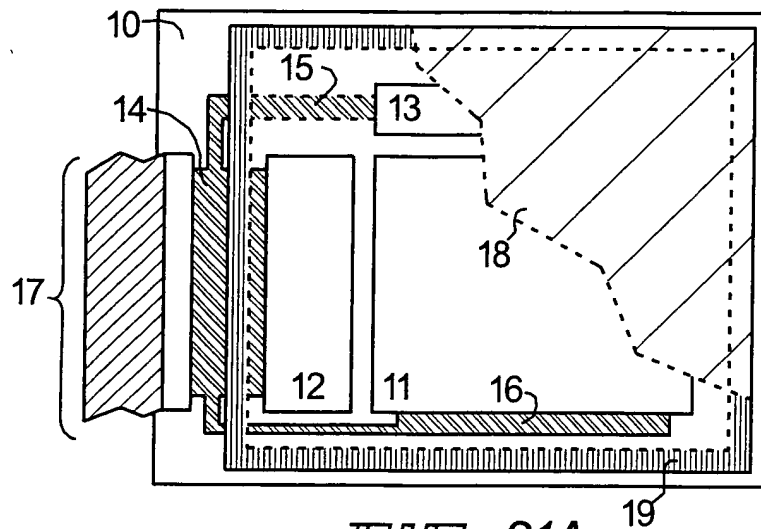


FIG. 21A

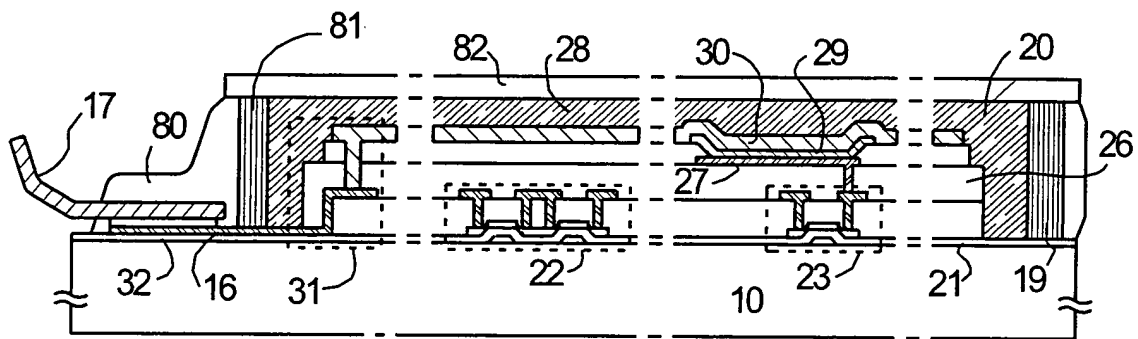


FIG. 21B

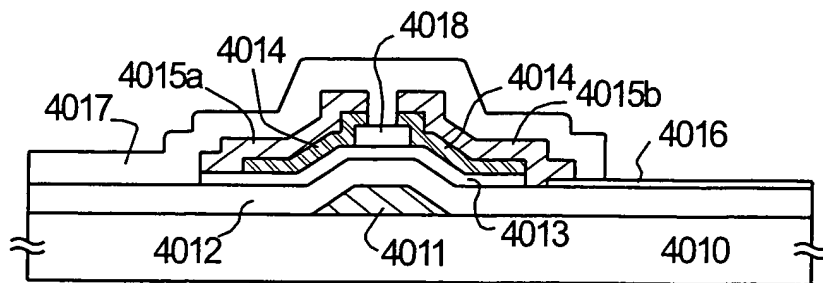


FIG. 22